

RD50 Common project proposal:

# Mobility of carriers in irradiated Silicon

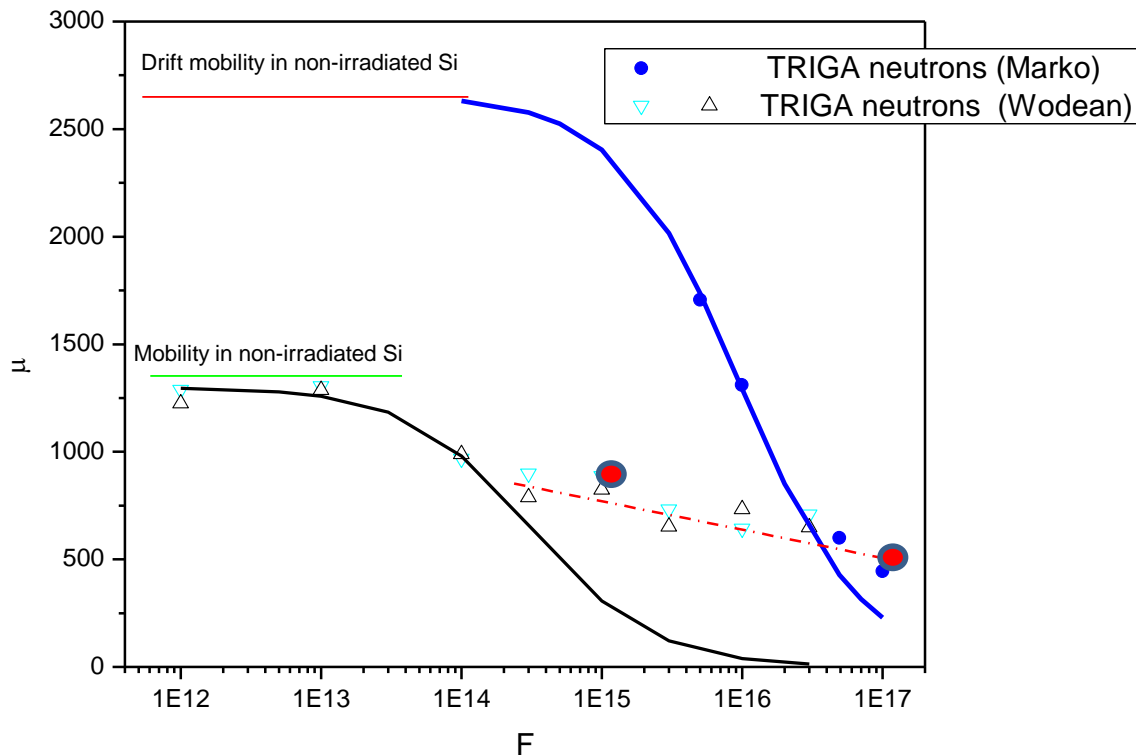
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The aim of this RD50 Common Project is to create a data base about **free carrier mobility dependence on fluence and electric field in differently irradiated silicon.**

- Vilnius University team is ready to measure these dependences of mobility of carriers by magnetoresistance means in the microstrip samples.
- We also will measure the deep levels (0.5 eV and deeper) by photoconductivity spectral dependence.

# The discussions on the mobility dependence on irradiation fluence have been started at 26<sup>th</sup> and 27<sup>th</sup> RD50 Workshops

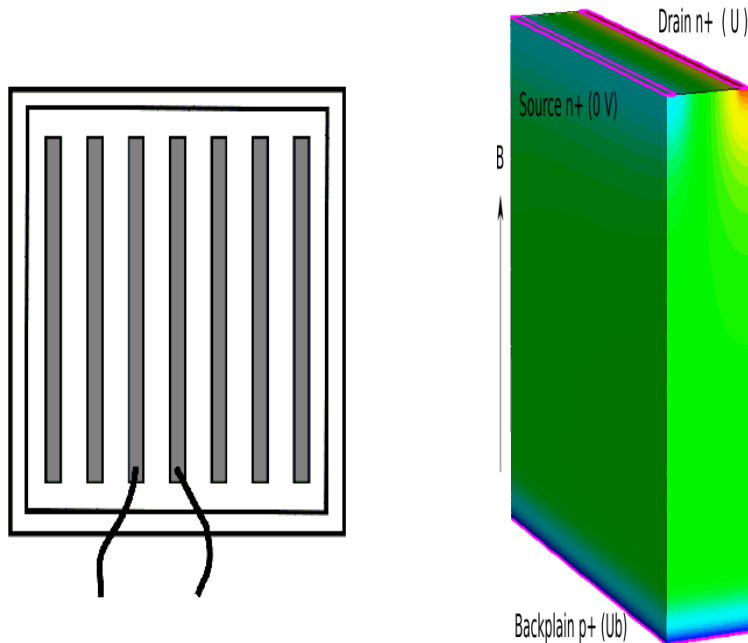


- Marko Mikuz demonstrated the indirect measurement of mobility in the highly irradiated Si, and approximated it as a square root dependence on the fluence.
- The mobility values in the samples irradiated to the fluence  $1e16$ - $1e17$  cm<sup>-2</sup> were similar to our measurements of magnetoresistance mobility in low E.
- It was decided to perform more detail measurements in the microstrip samples.

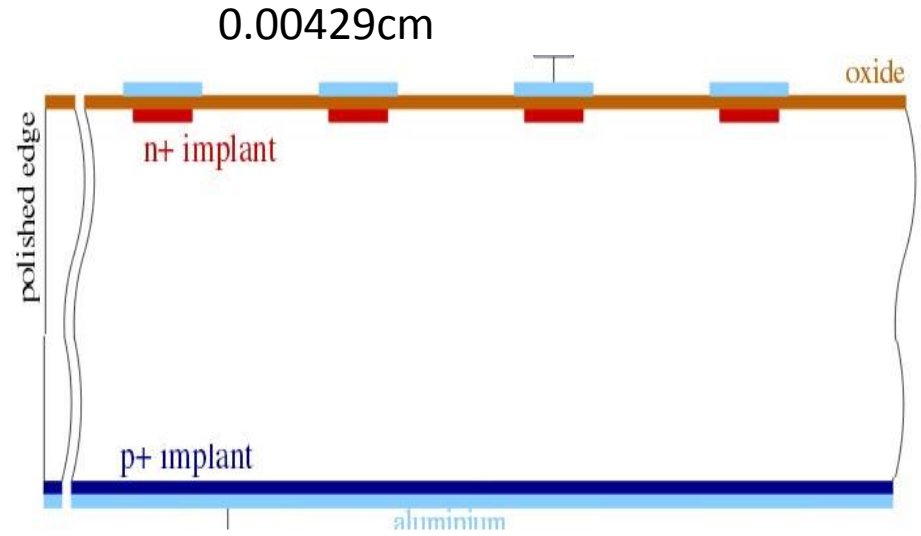
- Red dots - high E field, microstrip samples

The samples: standard microstrips, given by Ljubljana U group.

Silicon strip detectors on Float Zone (FZ) and Magnetic Czochralsky (MCz) were irradiated by fast neutrons with the fluence up to  $10^{17}$  n/cm<sup>2</sup>.



$L/W = 0,0043$ , that is very near to the Corbino dick value, and magnetoresistance effect will be maximal

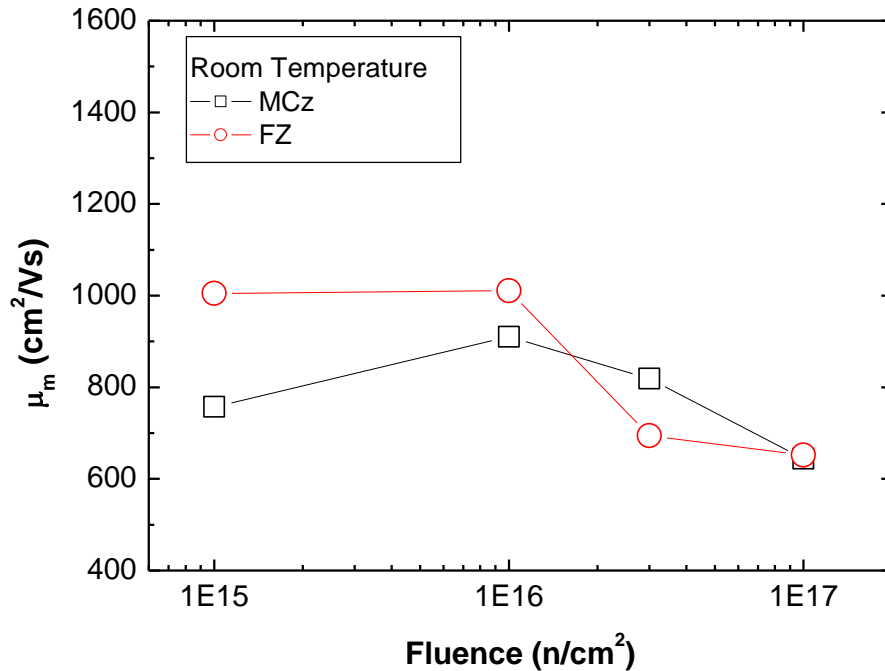


It was necessary to:

break down the oxide level;

It would be nice to remove the rear layers

# Mobility dependence on neutron fluence



$1/\mu = 1/\mu_{\text{phonons}} + 1/\mu_{\text{impurities}}$   
 $\mu_{\text{phonons}}$  decreases with E,  
 $\mu_{\text{impurities}}$  increases with E,  
if impurity is charged.

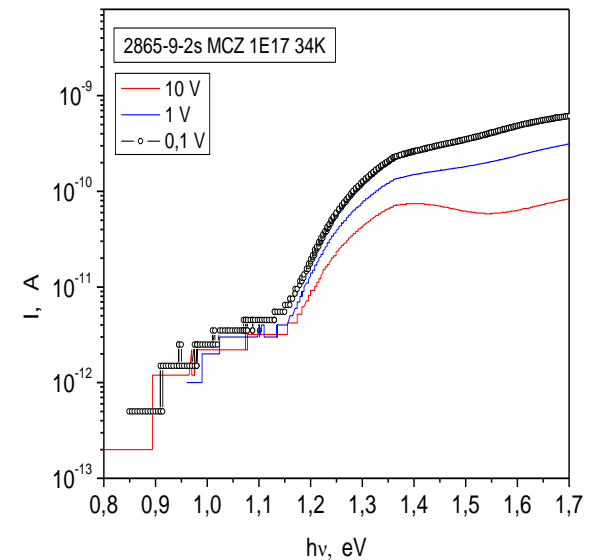
- Samples were irradiated in TRIGA reactor

We are ready to measure magnetoresistance mobility and its temperature dependence in the microstrip samples.

- We ask the partners to find in your boxes or frigs the differently irradiated Si microstrip structures.
  - It would be better :
    - if the DC coupling would be possible;
    - If the rear structure would be removed to have only the Si with microstrip contacts. This structure corresponds to the requirements for the magnetoresistance measurements.
- Therefore the partners' contribution:
  - 1. A time to find the samples;
  - 2. To realize DC coupling (if microstrip with AC coupling we used a breakdown at forward direction microstrip-pad.)
  - 3. The cost of etching of the back contact.
  - (Maybe there is a laboratory which could etch all samples?)

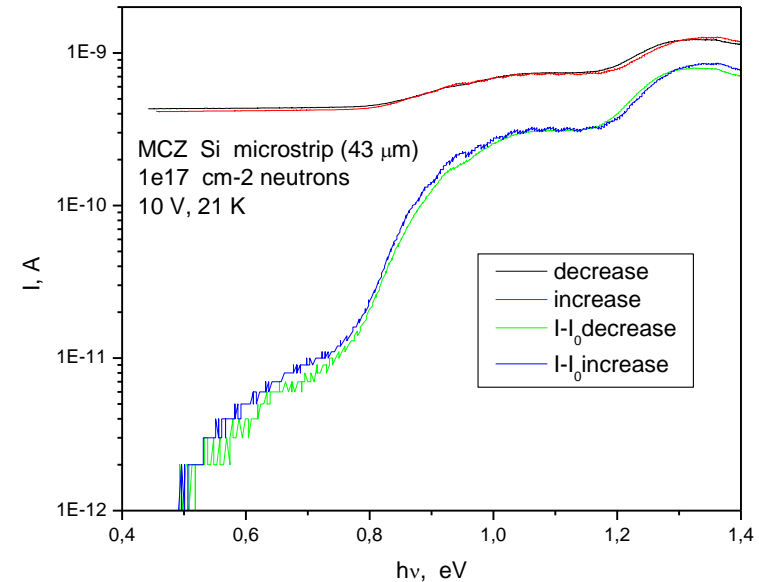
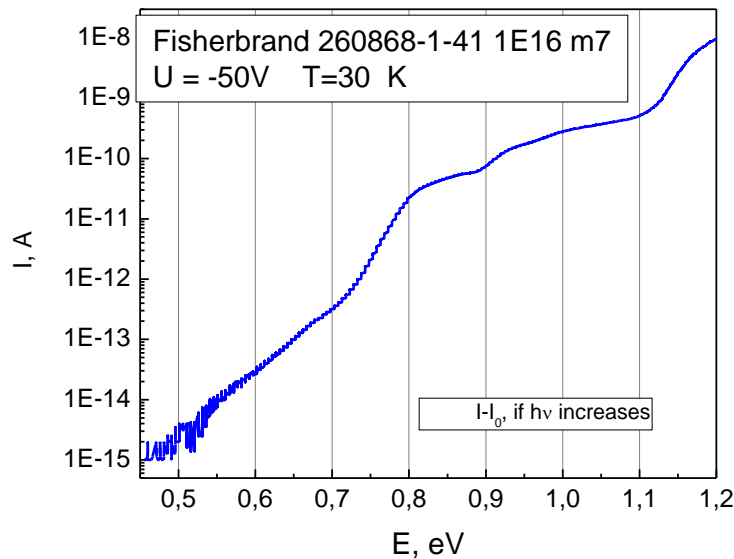
# Additional possibilities:

- As there is an interest to understand the influence of a charge in SiO<sub>2</sub> layer, it is possible to introduce or remove charge in it by electrostatic charging (and measure the magnetoresistance effect).
- The charge in SiO<sub>2</sub> layer influence can be controlled by photoconductivity by PC spectrum.



The deep level energy can be determined by PC spectra in the impurity region.

# Additional option: deep level energies by PC spectra



- $E_C-0.458$
- $E_C-0.545$
- $E_V+0.48=1.17-0.48=E_C-0.69$
- $E_V+0.36=1.17-0.36=E_C-0.81$
- $E_C-0.1=E_V+1.05$ , absent at  $T=30K$ , appears at  $T>120 K$

## Result of tuning: Hamburg Penta Trap Model (HPTM)

Defect	Type	Energy	$g_{int}$ [cm <sup>-1</sup> ]	$\sigma_e$ [cm <sup>2</sup> ]	$\sigma_h$ [cm <sup>2</sup> ]
E30K	Donor	$E_C-0.1$ eV	0.0497	2.300E-14	2.920E-16
V <sub>3</sub>	Acceptor	$E_C-0.458$ eV	0.6447	2.551E-14	1.511E-13
I <sub>p</sub>	Acceptor	$E_C-0.545$ eV	0.4335	4.478E-15	6.709E-15
H220	Donor	$E_V+0.48$ eV	0.5978	4.166E-15	1.965E-16
C <sub>i</sub> O <sub>i</sub>	Donor	$E_V+0.36$ eV	0.3780	3.230E-17	2.036E-14

- Trap concentration of defects:  $N = g_{int} \cdot \Phi_{neq}$
- Simulations for the optimization have been performed at  $T= -20$  °C with:
  1. Slotboom band gap narrowing
  2. Impact ionisation (van Overstaeten-de Man)
  3. TAT Hurkx with tunnel mass =  $0.25 m_e$  (default value:  $0.5 m_e$ ) in case of the I<sub>p</sub>
  4. Relative permittivity of silicon = 11.9 (default value : 11.9)
- Both cross section for the E30K and the electron cross section for the C<sub>i</sub>O<sub>i</sub> were fixed  
→ 12 free parameter
- Optimization done with the nonlinear simplex method



# Conclussion

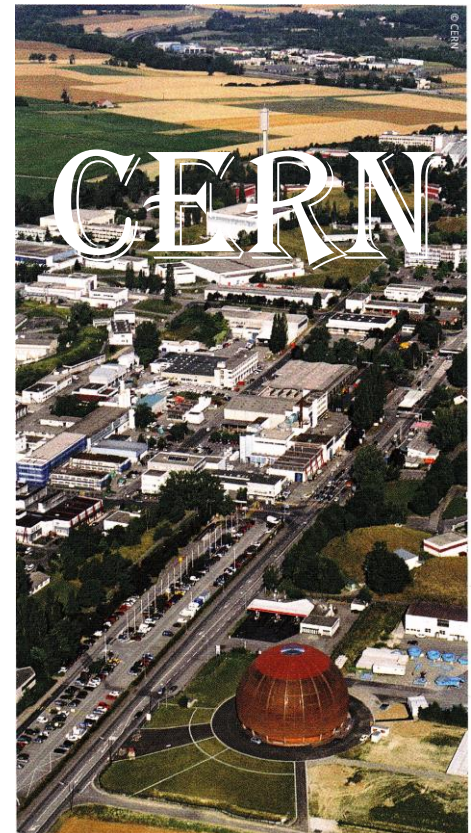
- As there was demonstrated it exist a few possibilities to measure or evaluate the mobility, I invite all to join this common project to perform the systematic analysis.

# Acknowledgements

## Thanks:

to Institute for Photonics and Nanotechnology (VU) for the partial support  
and  
to AIDA Transnational Access for irradiations in Triga reactor (Ljubljana)

THANK YOU  
FOR YOUR ATTENTION!



# Mobility dependence on sample bias, average E, V/cm

